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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(use as many sheets as necessary)

Sheet 1 of 1

Complete if Known

Application Number	10/729,511
Filing Date	December 4, 2003
First Named Inventor	Gregory BREYTA et al.
Art Unit	1713
Examiner Name	Unassigned
Attorney Docket Number	ARC920030073US1

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
YV	AA	3,444,148	5/13/69	Adelman			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
YV	AB	WO 01/86352	11/15/01	PCT			
YV	AC	WO 02/079287	10/10/02	PCT			
YV	AD	WO 03/040827	5/15/03	PCT			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
YV	AE	BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):613-620.	
YV	AF	FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," <i>Advances in Resist Technology And Processing XVIII, Proceedings of SPIE</i> 4345:296-307.	
YV	AG	ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE</i> 4345:273-284.	
YV	AH	KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:285-295.	
YV	AI	URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," <i>The Journal of Organic Chemistry</i> 33(6):2302-2310.	

Examiner Signature	/Yevgeny Valenrod/	Date Considered	11/14/2006
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.